AZ® 10XT Photoresist

Thick Positive Novolak Photoresist

For Plating and Etch Applications

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AZ® 10XT Photoresist

- AZ® 10XT positive photoresist is designed for 5 to 25 micron film thickness in high performance rerouting processes and other plating applications.
- Three viscosities are available to cover a variety of film thicknesses.
- PFOS free formulation.
- Excellent coat capability, 3 to 1 aspect ratios, vertical sidewalls.
- Sensitive to g, h and i-line wavelengths
- Compatible with both inorganic and organic developers. Shorter develop times can be realized with inorganic developers, however.

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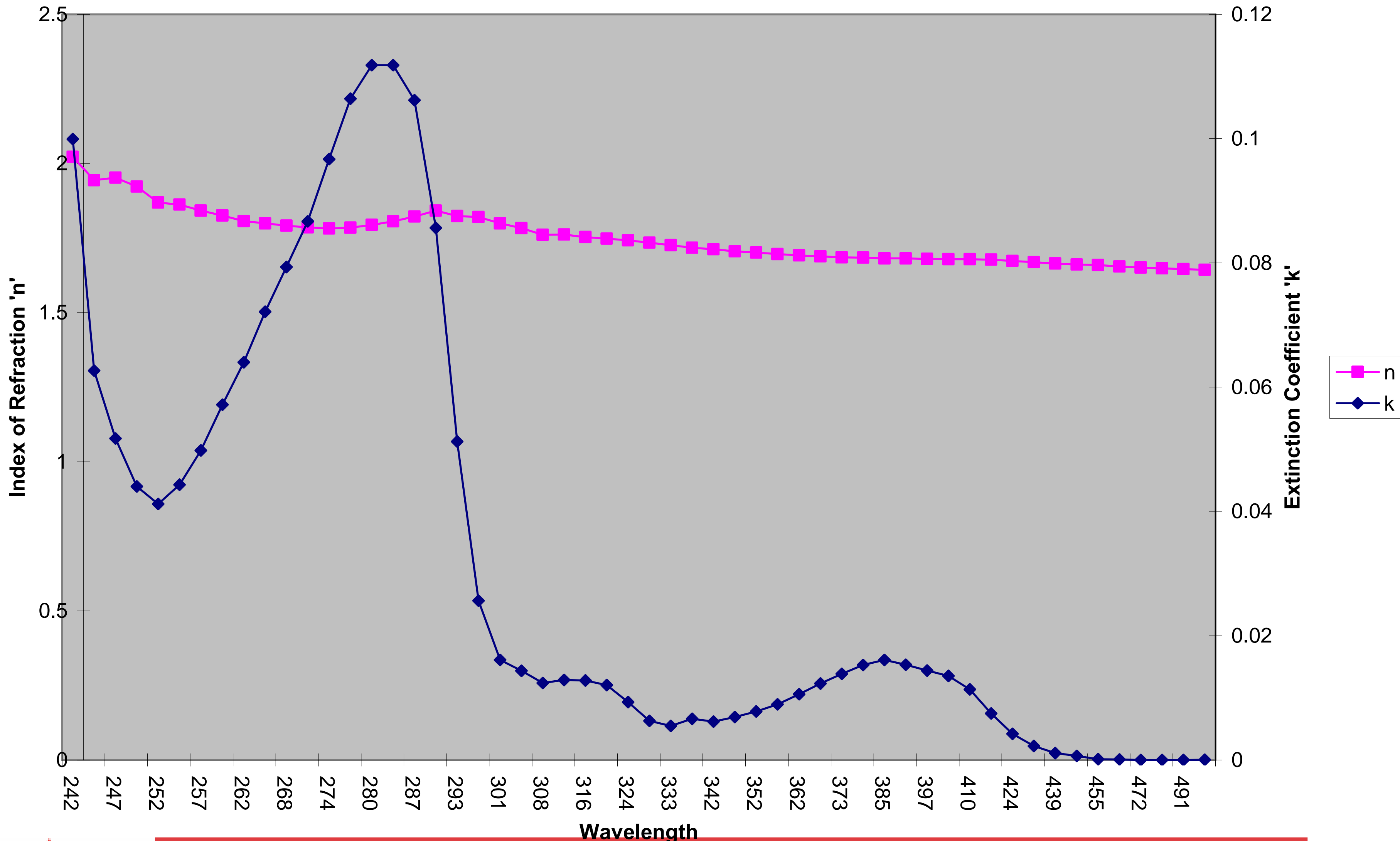
AZ® 10 XT Photoresist

Optical Constants (n & k)



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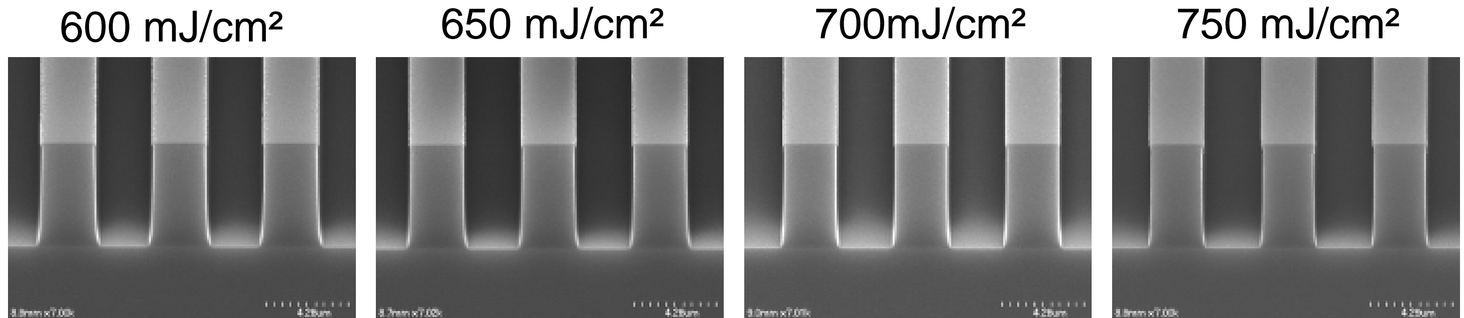
AZ® 10XT Photoresist, FT=6 µm

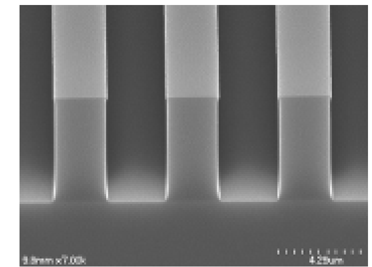
3.0 µm L/S Exposure Latitude on Silicon

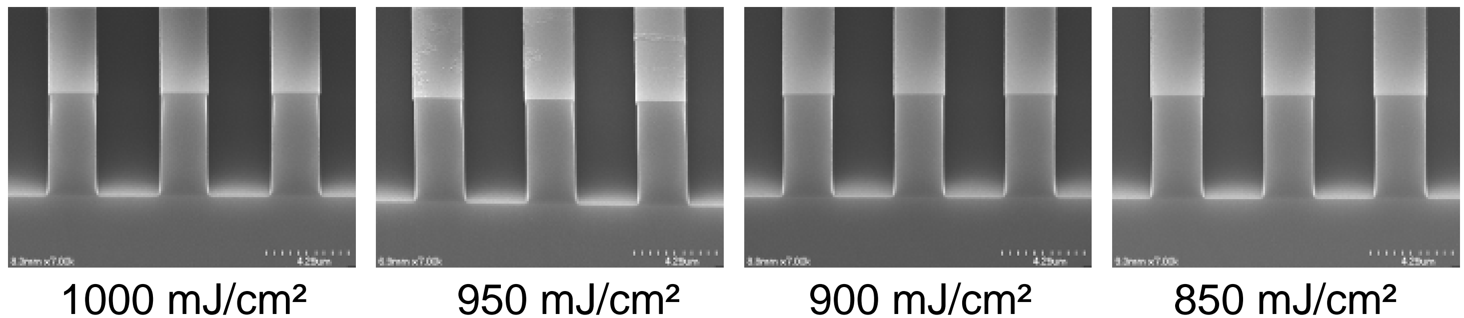
600 mJ/cm² 650 mJ/cm² 700mJ/cm² 750 mJ/cm²



Optitrac coat and Bake
SB: 110°C/ 120 sec
Ultratech 1500 gh line stepper
AZ 400K 1:4 / 420 sec immersion @ 23 °C

800 mJ/cm²





1000 mJ/cm² 950 mJ/cm² 900 mJ/cm² 850 mJ/cm²

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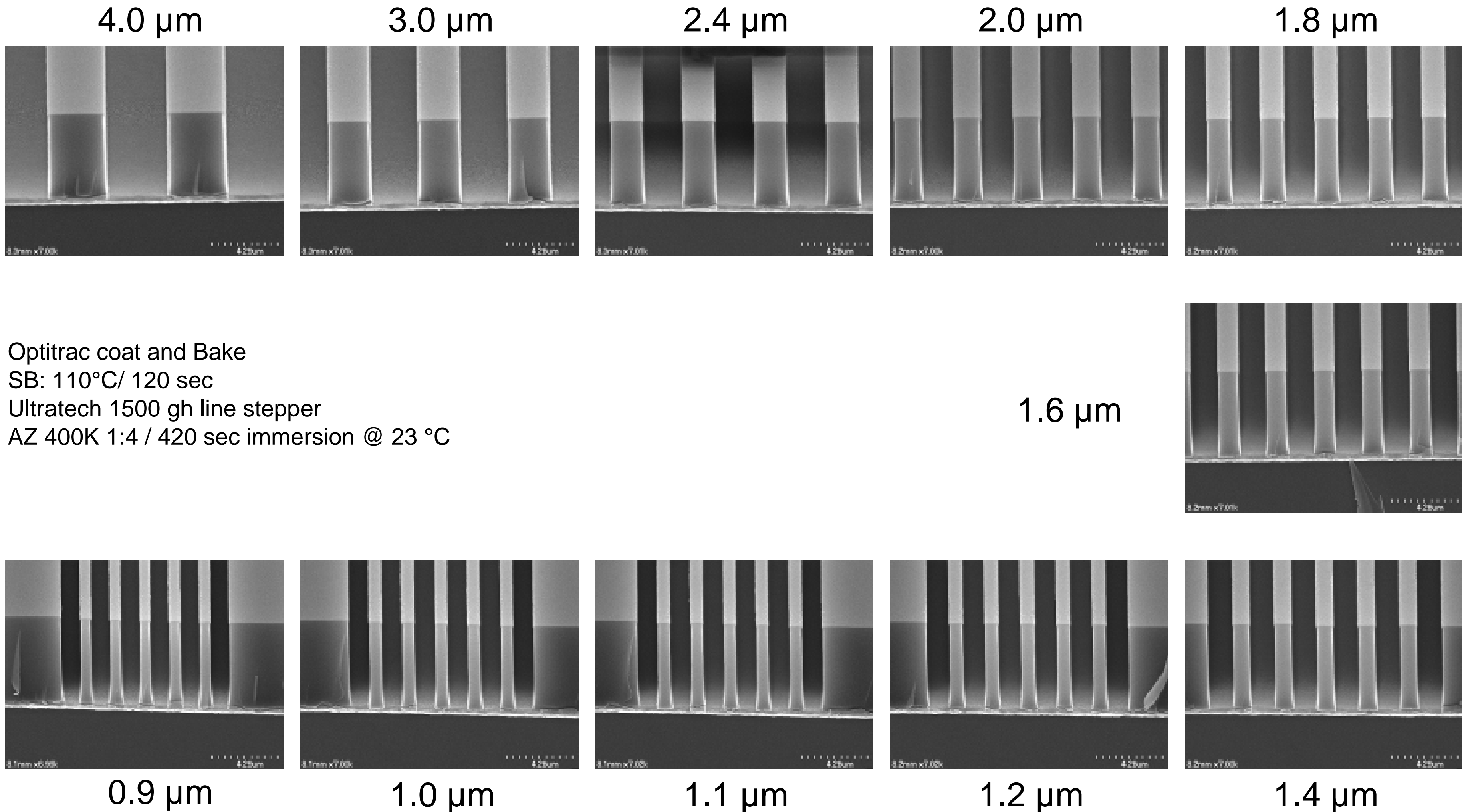
AZ® 10XT Photoresist, FT=6 µm

Linearity on Copper @ 850 mJ/cm²



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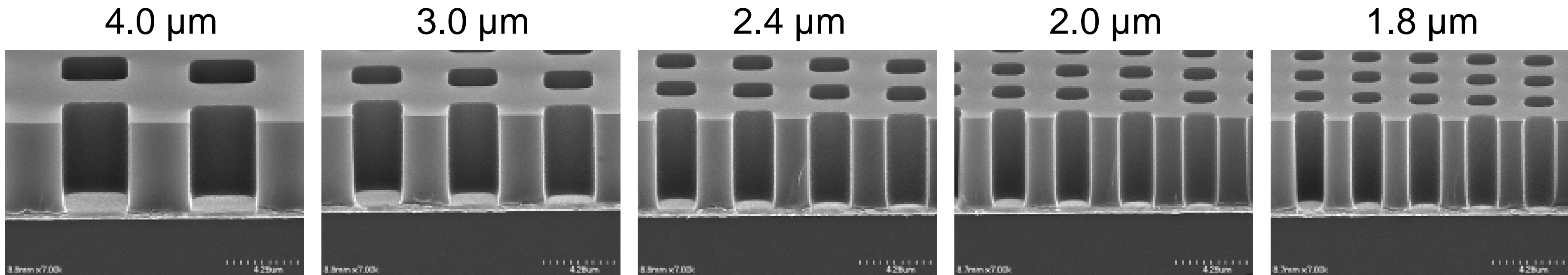
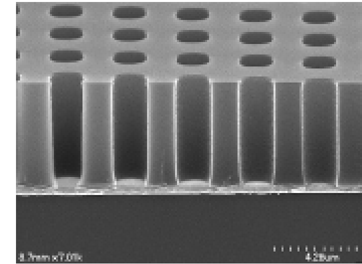
AZ® 10XT Photoresist, FT=6 µm

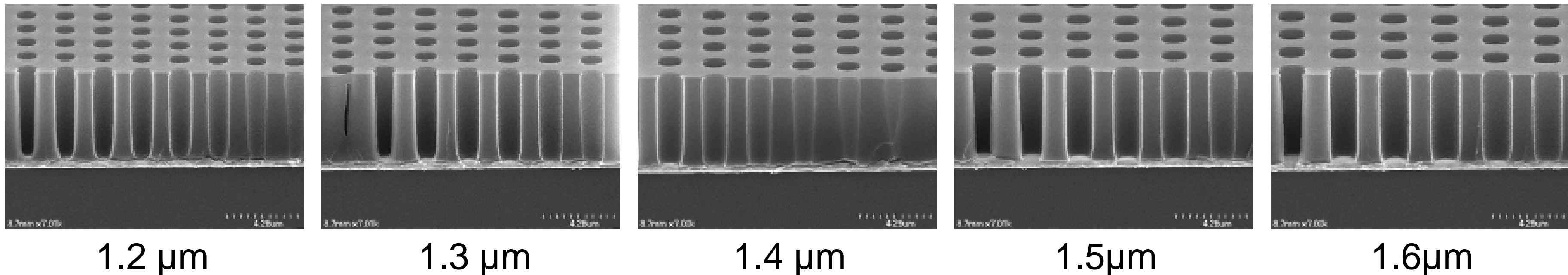
CH Linearity on Copper @ 800 mJ/cm²



Optitrac coat and Bake
SB: 120°C/ 120 sec
Ultratech 1500 gh line stepper
AZ 400K 1:4 / 420 sec immersion @ 23 °C

1.7 µm





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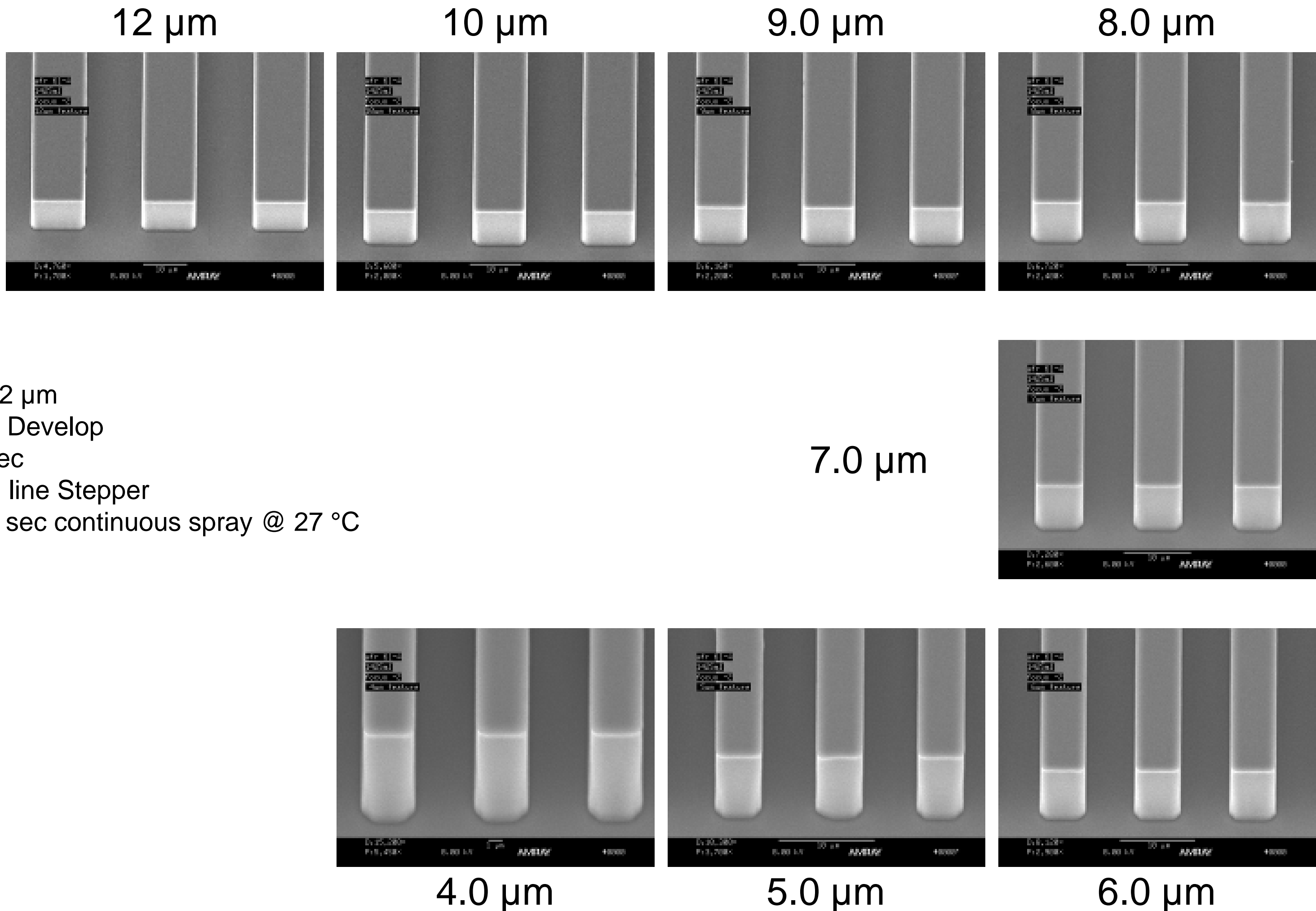
AZ® 10XT Photoresist, FT=12 µm

Linearity on Silicon @ 1425 mJ/cm²



Film Thickness: 12 µm
Optitrac Coat and Develop
SB: 110°C/ 180 sec
Ultratech 1500 gh line Stepper
AZ 400K 1:4, 260 sec continuous spray @ 27 °C

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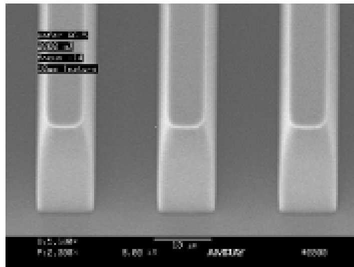
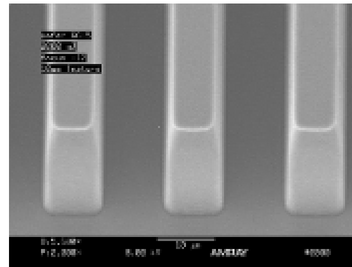
AZ® 10XT Photoresist, FT=24 µm

Depth of Focus @ 2000 mJ/cm², 10.0 µm L/S

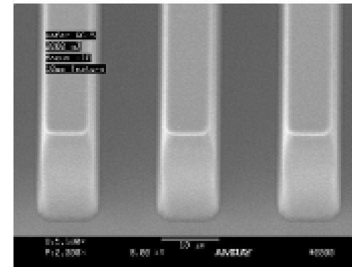
-14.0 µm



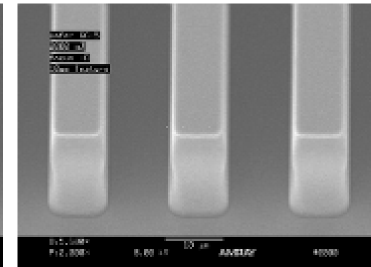
-12.0 µm



-10.0 µm

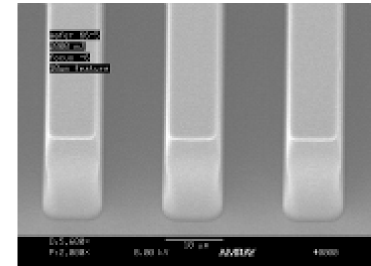


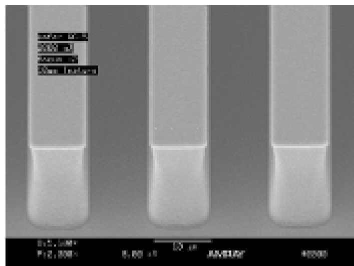
-8.0 µm



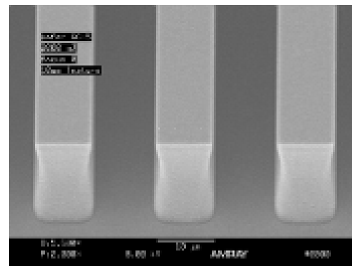
Optitrac Coat and Bake
SB: 1st layer 110°C/ 80 sec
2nd layer 115°C/180 sec
Ultratech 1500 gh line Stepper
AZ 400K 1:4, 600 sec continuous spray @ 27 °C

-6.0 µm

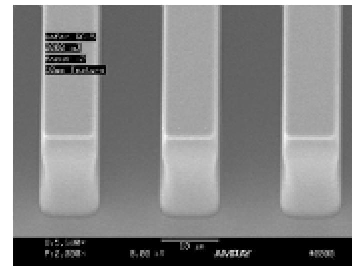




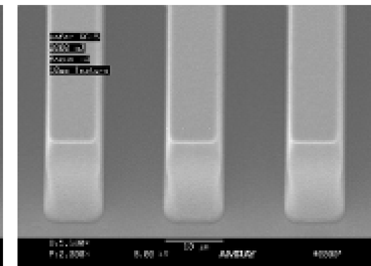
2.0 µm



0.0 µm



-2.0 µm



-4.0 µm

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